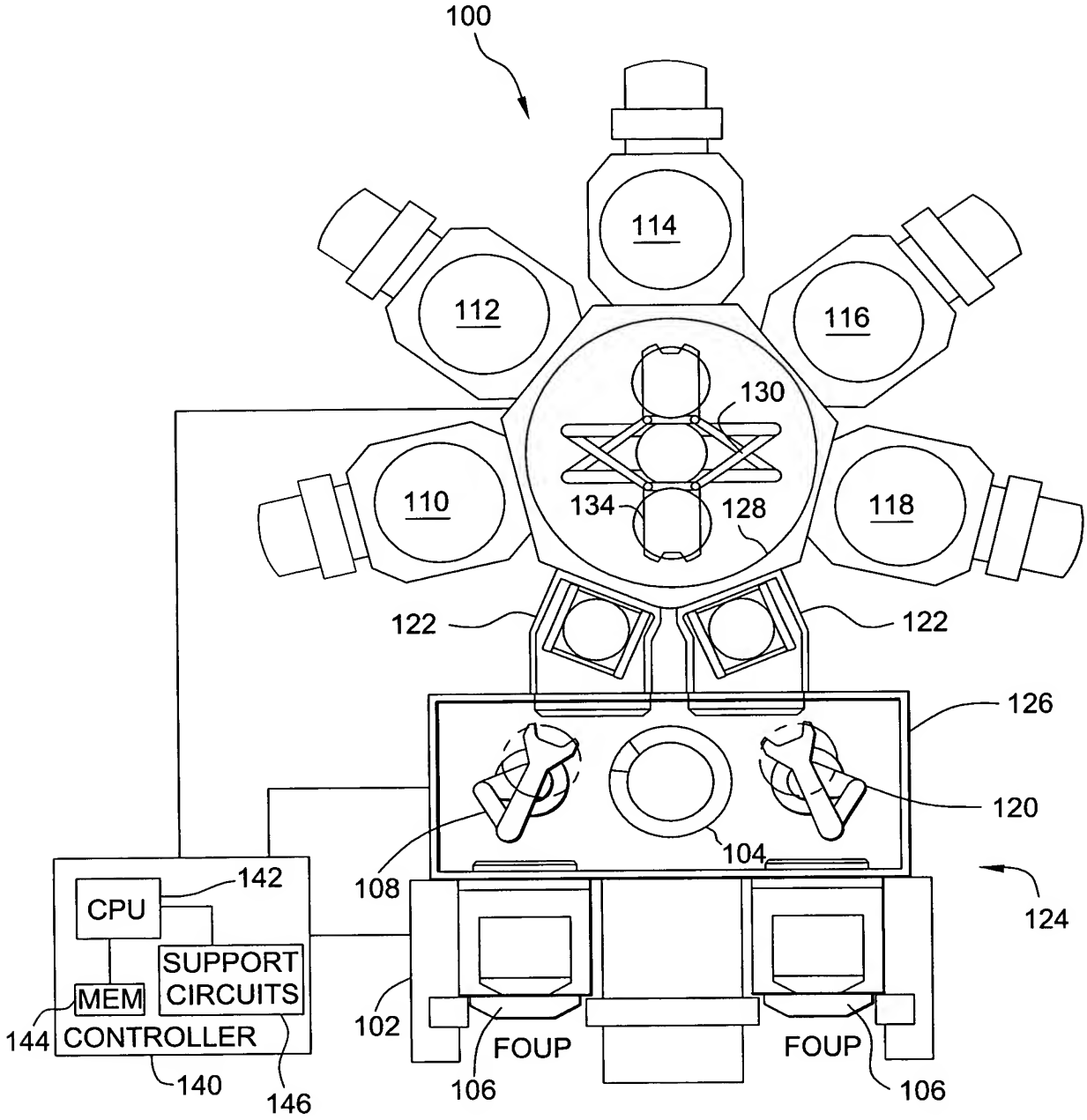
100
114
112
116
130
110
134
128
118
122
122
126
120
104
108
124
142
CPU
SUPPORT CIRCUITS
MEM
144
CONTROLLER
140
146
102
FOUP
106
FOUP
106

FIG. 1

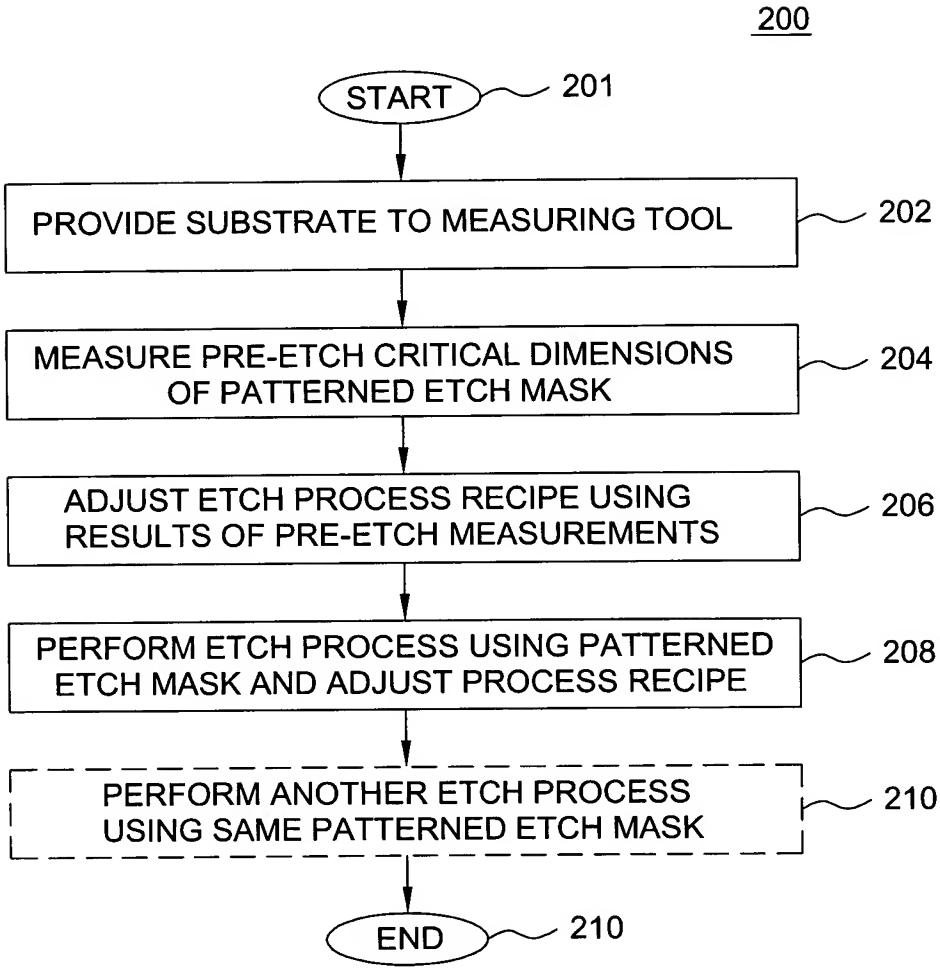
200
START
201
PROVIDE SUBSTRATE TO MEASURING TOOL
202
MEASURE PRE-ETCH CRITICAL DIMENSIONS OF PATTERNED ETCH MASK
204
ADJUST ETCH PROCESS RECIPE USING RESULTS OF PRE-ETCH MEASUREMENTS
206
PERFORM ETCH PROCESS USING PATTERNED ETCH MASK AND ADJUST PROCESS RECIPE
208
PERFORM ANOTHER ETCH PROCESS USING SAME PATTERNED ETCH MASK
210
END
210

FIG. 2

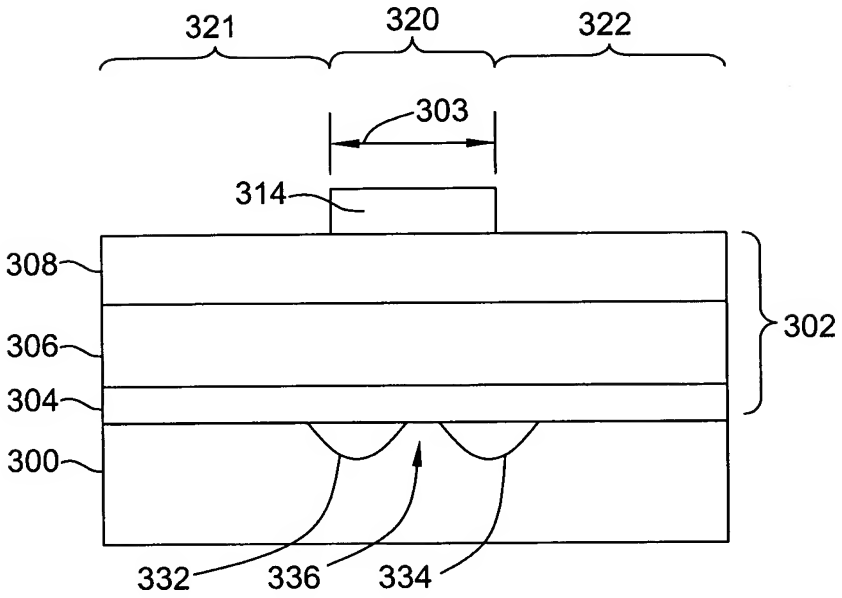
321
320
322
303
314
308
306
304
300
302
332
336
334

FIG. 3A

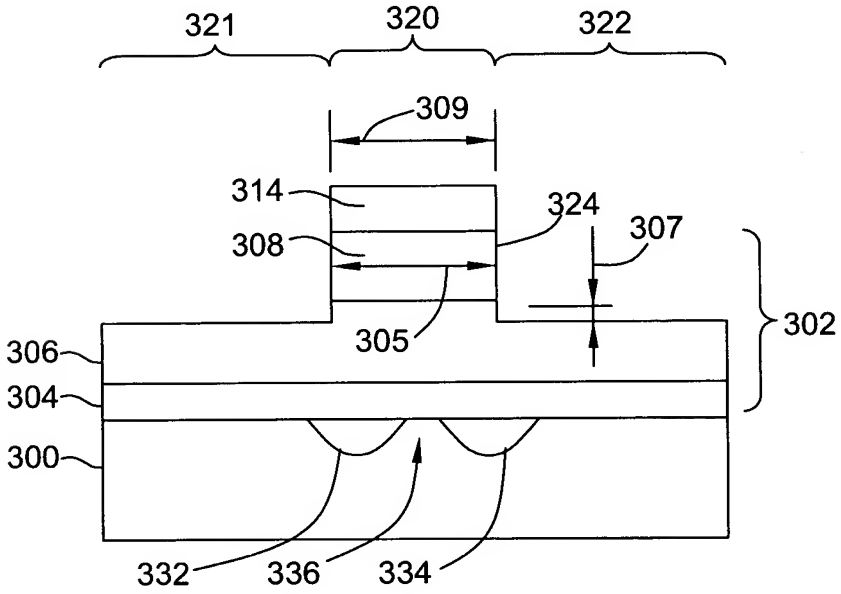
321
320
322
309
314
324
307
308
305
306
304
300
302
332
336
334

FIG. 3B

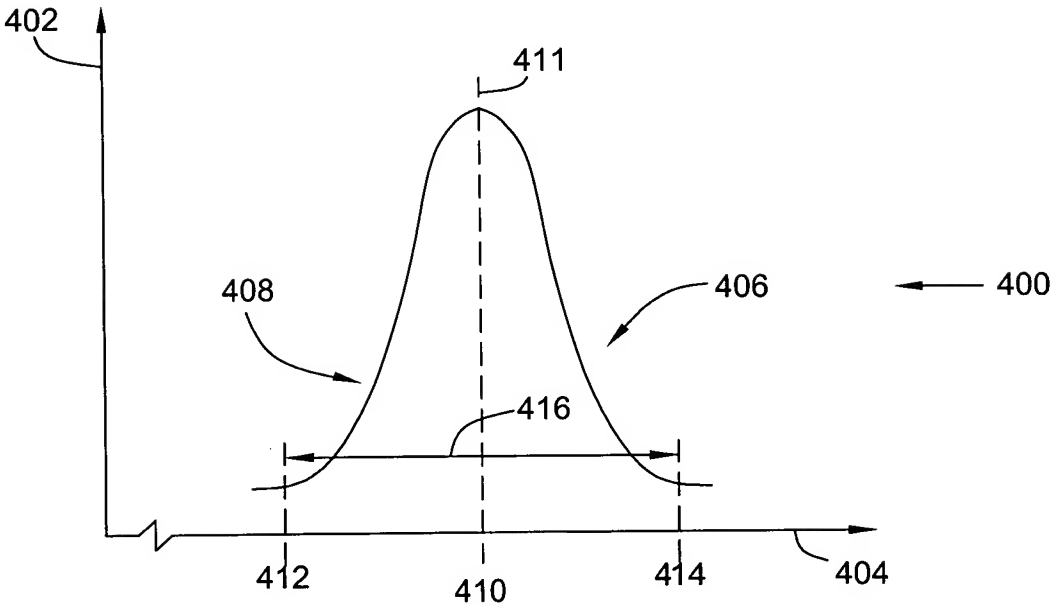
402
411
408
406
400
416
412
410
414
404

FIG. 4A

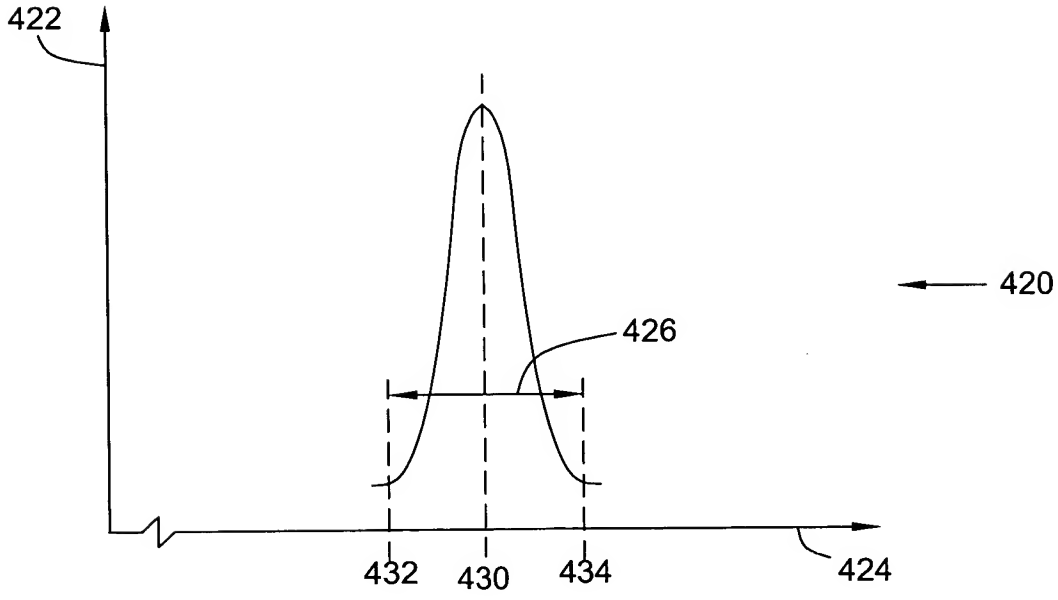
422
420
426
432
430
434
424

FIG. 4B

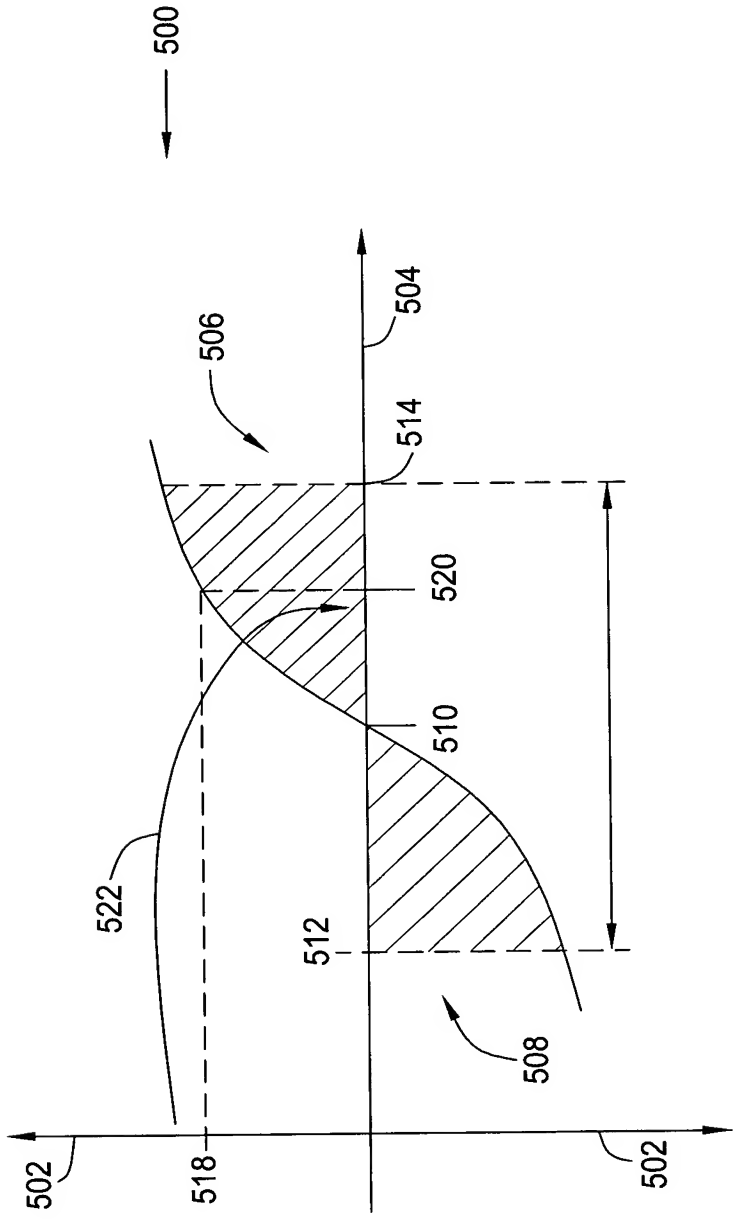


FIG. 5

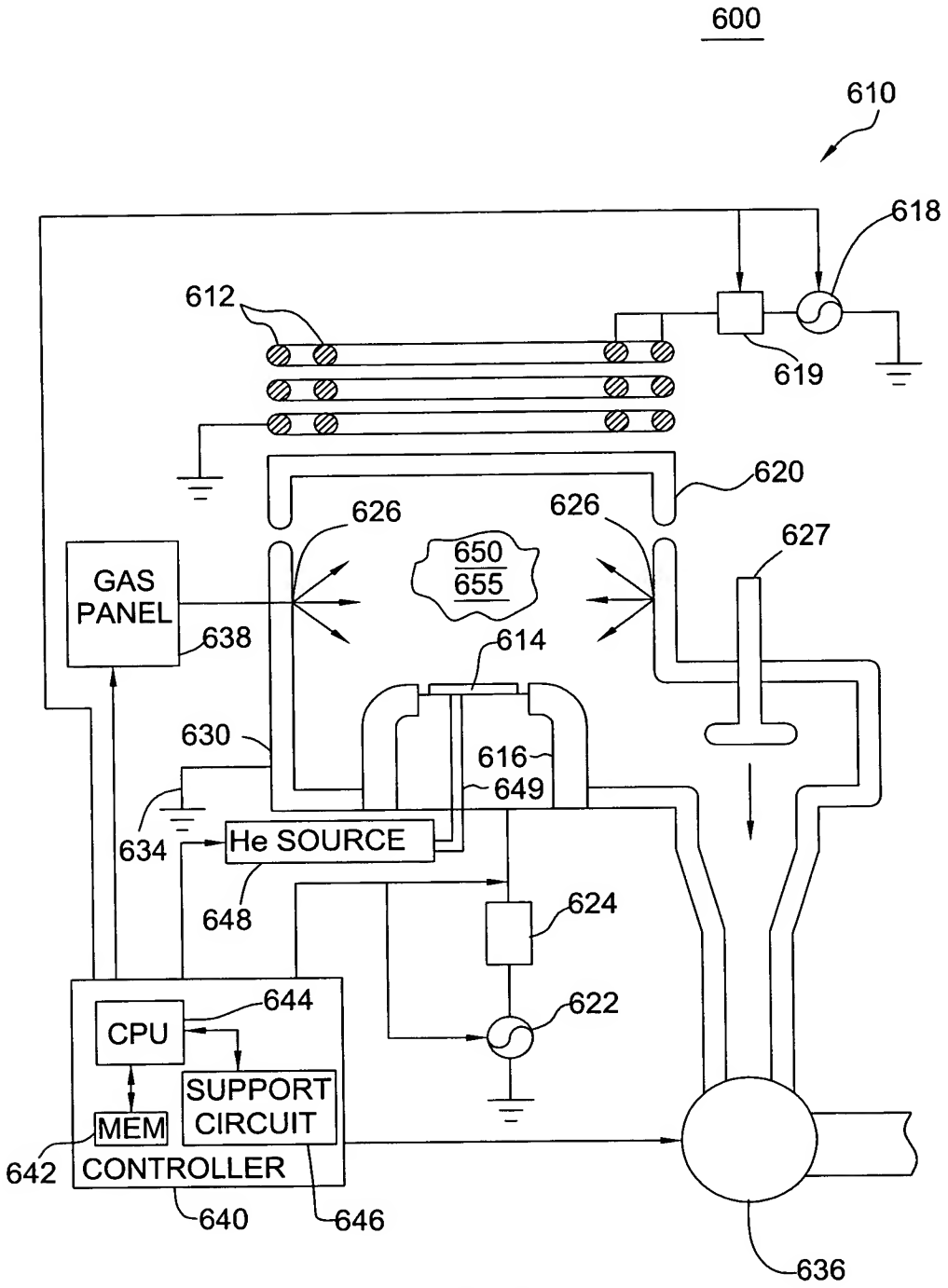
600
610
618
612
619
620
626
626
627
650
655
GAS PANEL
638
614
630
616
649
634
He SOURCE
648
624
622
644
CPU
SUPPORT CIRCUIT
MEM
642
CONTROLLER
640
646
636

FIG.6